# Monthly LabAdviser update: 27/9 2013

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| Updated Subject  | Contributor | Link to the update pages |
| **New equipment in the pipeline and old equipment for decommissioning**This page has been updated. Here you can see what the plans are for the comming year with regards to new equipment coming in and old equipment going out. | **Danchip management** | <http://labadviser.danchip.dtu.dk/index.php/LabAdviser/New_equipment_in_the_pipeline_and_Old_equipment_for_decommissioning> |
| **Lithography**New start page for the lithography at Danchip, comparing photolithography, DUV lithography and E-beam lithography,(To come: Nanoimprint lithography and 2-photon lithography) | Making the structure of this entry: **Tine Greibe @danchip****Elena Khomtchenko @danchip** has also add info to this page | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Lithography#Comparing_lithography_methods_at_DTU_Danchip> |
| **DUV stepper and spinner**Information about DUV lithography at Danchip. Equipment info on the DUV stepper and the Süss Spinner-Stepper. | Elena Khomtchenko**Matthias Keil** **Tine Greibe****@danchip** | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Lithography/DUVStepperLithography> |
| **E-beam**New updated page about e-beam lithography at Danchip | Tine Greibe @danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Lithography/EBeamLithography> |
| **UV-lithography**New UV lithography entry including information about the new resists on the new spin track | Elena Khomtchenko**Thomas A. Anhøj****Tine Greibe****@danchip** | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Lithography/UVLithography> |
| **New Spin Track 1+2**Information on the new spin track installed in cleanroom 3 has been added. Including process information on the two new resists: AZ MiR 701 and AZ nLOF 2020 | Thomas Anhøj@ danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Lithography/Coaters#Spin_Track_1_.2B_2><http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Lithography/Coaters/Spin_Track_1_%2B_2_processing> |
| **Spin dryers**Equipment page on the spin dryers has been added | Jens Hemmingsen @danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Lithography/WaferCleaning#Spindryers> |
| **KOH1**KOH1 will from now on be dedicated for wafers with electroplated nickel or otherwise dirty wafers. | Karen Birkelund @danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/KOH_Etch> |
| **AOE etching of fused silica**Added test with Cr mask and some SEM images of the etched profiles. | Berit G. Herstrøm @danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Etching_of_Bulk_Glass/AOE_etching_of_fused_silica> |
| **How to pattern TiO2**A short comment on how to pattern TiO2 deposited in the IBE/IBSD Ionfab | Berit G. Herstrøm @danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Thin_film_deposition/Deposition_of_Titanium_Oxide/IBSD_of_TiO2#How_to_pattern_TiO2> |
| **AOE slow etch of SiO2 with carrier**Due to the decommissioning of RIE1 we are looking into a slow SiO2 etch where the sample can be placed on a Si carrier. | Berit G. Herstrøm @danchip | <http://labadviser.danchip.dtu.dk/index.php/Specific_Process_Knowledge/Etch/Etching_of_Silicon_Oxide/SiO2_etch_using_AOE#Slow_etch_of_SiO2_with_resist_as_masking_material_-_to_be_used_with_150mm_Si_carrier_wafer> |